#### Lecture11: MOSFET IV

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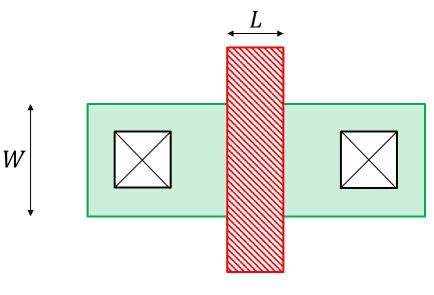
### Q&A

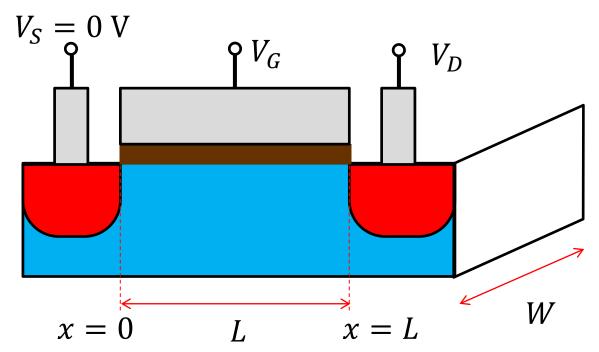
- Various definition of  $V_{TH}$ ?
  - Which is the exact one?

- Linear  $Q_{elec} V_G$  relation. Why?
  - Surface potential pinning

### **Device structure**

- 2D cross-section
  - "Potential" can be dependent on the position, V(x).





## Our goal: IV relation

#### Current densities

In the 1D structure (along the x direction),

$$J_{n,x}^{diff} = qD_n \frac{dn}{dx}$$
$$J_{n,x}^{drift} = q\mu_n n E_x$$

We assume that the drift current is dominant.

#### Terminal current

- A correct sign!
- In the 1D structure, the drain current would be

$$I_D = -Area \times \left(J_{n,x}^{diff} + J_{n,x}^{drift}\right)$$

Electron is not uniformly distributed along the vertical direction.

# **Derivation of IV (1)**

#### Drain current

- $Q_{elec}$  is the electron charge density *per unit length*.
- It follows (with a correct sign)

$$Q_{elec} = -WC_{ox}[V_G - V(x) - V_{TH}]$$
 (Razavi 6.3)

- At a certain position of x, the current is given by

$$I(x) = Q_{elec}(x) v(x)$$
 (Razavi 6.4)

Also v is the electron velocity.

$$v = -\mu_n E = +\mu_n \frac{dV}{dx}$$
 (Razavi 6.5 and 6.6)

# **Derivation of IV (2)**

- Drain current (Continued)
  - It is easy to understand that  $I_D = -I(x)$ .
  - The drain current is

$$I_D = WC_{ox}[V_G - V(x) - V_{TH}]\mu_n \frac{dV}{dx}$$
 (Razavi 6.7)

Simply re-arranging,

$$I_D dx = \mu_n C_{OX} W[V_G - V(x) - V_{TH}] dV$$

When integrated,

$$I_D = \mu_n C_{ox} \frac{W}{L} \left[ (V_G - V_{TH}) V_{DS} - \frac{1}{2} V_{DS}^2 \right]$$

## Differential equation

#### Equation

- A differential equation for V(x)

$$I_D = WC_{ox}[V_G - V(x) - V_{TH}]\mu_n \frac{dV}{dx}$$

– Let's solve it together!

### Its solution

#### Equation

Its solution

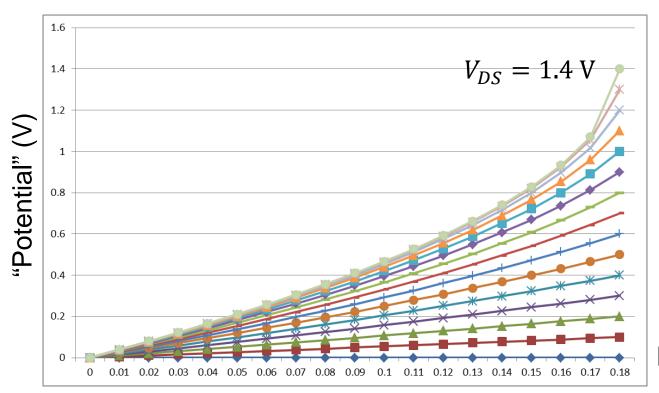
$$V(x) = V_G - V_{TH} - \sqrt{(V_G - V_{TH})^2 - \frac{2I_D}{\mu_n C_{ox} W}} x$$

- Apply boundary conditions:  $V(0) = V_S$  and  $V(L) = V_D$
- Drain current

$$I_D = \mu_n C_{ox} \frac{W}{L} \left[ (V_G - V_{TH}) V_{DS} - \frac{1}{2} V_{DS}^2 \right]$$

# Solution, "potential"

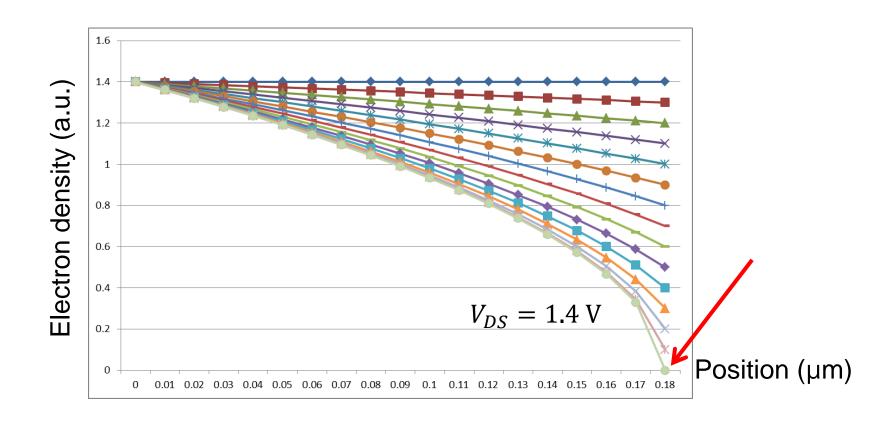
•  $V_{GS} = V_{DD} = 1.8 \text{ V}$ .  $V_{DS}$  from 0 V to  $V_{DD} - V_{TH} = 1.4 \text{ V}$ 



Position (µm)

## Solution, electron density

•  $V_{GS} = V_{DD} = 1.8 \text{ V}. V_{DS} \text{ from 0 V to } V_{DD} - V_{TH} = 1.4 \text{ V}$ 

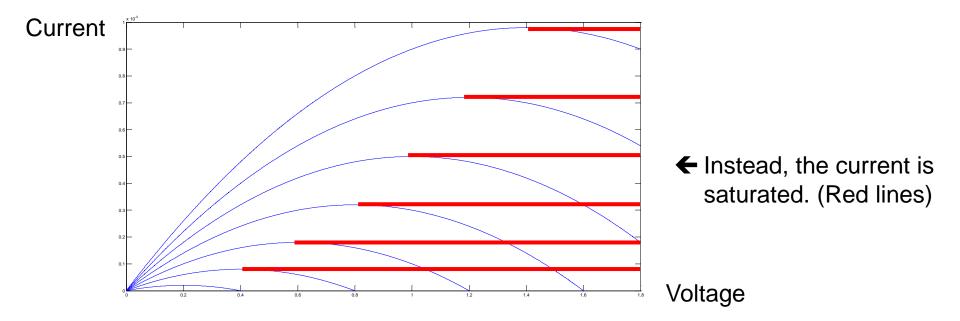


#### Saturation mode

Current usually increases as the voltage increases...

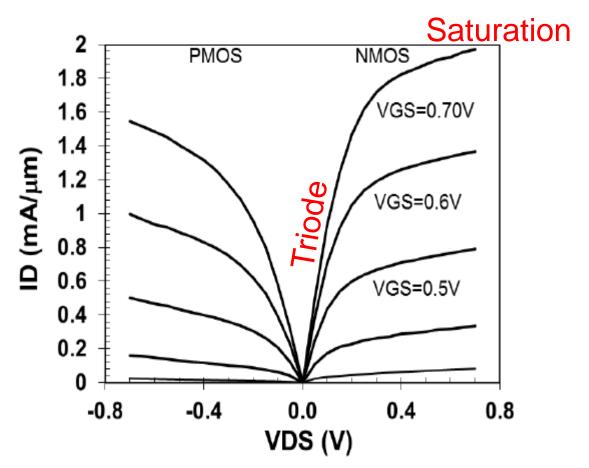
$$|Q_{elec}| = WC_{ox}[V_G - V(x) - V_{TH}]$$
 (Razavi 6.3)

- What happens when  $V(x) = V_G - V_{TH}$ ?



## State-of-the-art MOSFET (1)

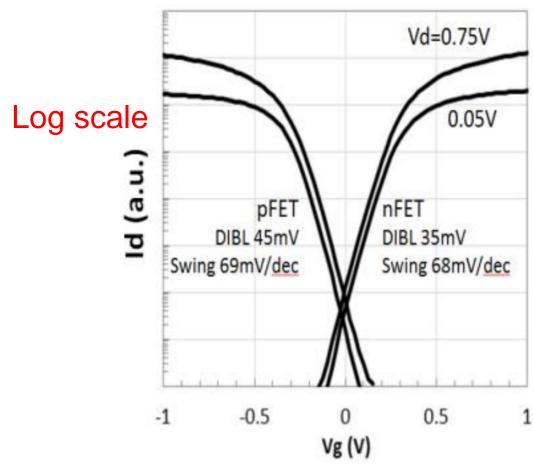
- C. Auth et al. (Intel, IEDM 2017)
  - Slight increase of  $I_D$  in the saturation region



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# State-of-the-art MOSFET (2)

- G. Yeap et al. (TSMC, IEDM 2019)
  - $I_D V_G$  curves (NMOSFET & PMOSFET)



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